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PTO-1219 (Modified) U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE  INFORMATION DISCLOSURE STATEMENT BY APPLICANT	ATTY. DOCKET NO. <b>213.007-US</b>	SERIAL NUMBER <b>10/815,573</b>
	APPLICANT(S) <b>Ye et al.</b>	
	FILING DATE <b>April 1, 2004</b>	FILING DATE <b>4756-2825</b>

## U.S. PATENT DOCUMENTS

EXAMINER INITIALS	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE
<i>P</i>	5,563,702	10/1996	Emery et al.			
<i>P</i>	5,737,072	4/1998	Emery et al.			

## FOREIGN PATENT DOCUMENTS

EXAMINER INITIALS	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION YES/NO

## OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

<i>P</i>	"Photomask Production Integration of KLA STARlight™ 3000 System", Kalk et al, Proc. Of SPIE, Vol. 2621, 15 <sup>th</sup> Annual BACUS Symposium on Photomask Technology and Management, December 1995, pp.112-121
<i>P</i>	"Defect Detection and Classification in VLSI Pattern Inspection", Soo-Ik Chae, September 1987, Ph.D. Dissertation, 117 pages

EXAMINER <i>Phallaka Kide</i>	DATE CONSIDERED <i>11/8/2005</i>
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	APPLICANT(S) Ye et al.	
	FILING DATE April 1, 2004	GROUP ART UNIT <del>1750</del> 2825

## U.S. PATENT DOCUMENTS

EXAMINER INITIALS	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE
<i>PJ</i>	2004/0096883	5/2004	Fiekowsky et al.	435	6	
<i>PJ</i>	6,090,555	7/2000	Fiekowsky et al.	435	6	
<i>PJ</i>	6,397,165	5/2002	Fiekowsky	702	157	
<i>PJ</i>	6,405,153	6/2002	Fiekowsky	702	172	
<i>PJ</i>	6,539,331	3/2003	Fiekowsky	702	159	
<i>PJ</i>	6,611,767	8/2003	Fiekowsky et al.	702	19	
<i>PJ</i>	6,760,473	7/2004	Fiekowsky	382	149	
<i>PJ</i>	6,765,651	7/2004	Fiekowsky et al.	355	77	

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PTO-1449 (Rev. 11/01/03) U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE  INFORMATION DISCLOSURE STATEMENT BY APPLICANT	ATTY. DOCKET NO. <b>213.007-US</b>	SERIAL NUMBER <b>10/815,573</b>
	APPLICANT(S) <b>Ye et al.</b>	
	FILING DATE <b>April 1, 2004</b>	GROUP ART UNIT <b>4750-2825</b>

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EXAMINER INITIALS	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE

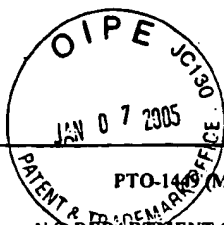
## FOREIGN PATENT DOCUMENTS

EXAMINER INITIALS	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION YES/NO

## OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

	"Compact Formulation of Mask Error Factor for Critical Dimension Control in Optical Lithography", Zhang, et al., Microlithography, SPIE 2002, 4 pages
	"A Simulation Framework for Lithography Process Monitoring and Control Using Scatterometry", Bao et al., AEC/APC 2001, 4 pages
	"A Novel Approach for Modeling and Diagnostics of Lithography Process", Wang et al., AEC/APC 2001, 5 pages
	"Optimum sampling for characterization of systematic variation in photolithography", Cain et al., Microlithography, SPIE 2002, 13 pages
	"Electrical linewidth metrology for systematic CD variation characterization and causal analysis", Cain et al., Microlithography, SPIE 2003, 12 pages

EXAMINER <b>Phallaka Kik</b>	DATE CONSIDERED <b>11/8/2005</b>
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	APPLICANT(S) <b>Ye et al.</b>	
	FILING DATE <b>April 1, 2004</b>	GROUP ART UNIT <b>4756 2825</b>

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EXAMINER INITIALS	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE

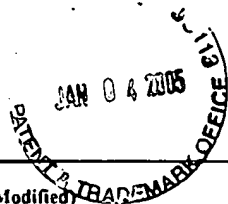
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EXAMINER INITIALS	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB CLASS	TRANSLATION YES/NO

## OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

	"Improved Method for Measuring and Assessing Reticle Pinhole Defects for the 100nm Lithography Node", Taylor et al., Photomask Japan 2002, April 2002, pp. 1-7.
	"Mask Defect Disposition: Flux-Area Measurement of Edge, Contact, and OPC Defects Correlates to Wafer and Enables Effective Decisions", Fiekowsky et al., Photomask Japan 2001, Paper 4409-10, April 2001, pp. 1-8.
	"Contact Holes: Optical Area Measurement Predicts Printability and is Highly Repeatable", By Glen Scheid, LSI Logic Corp.; Taylor et al., Photomask Japan 2001, Paper 4409-11, April 2001, pp. 1-6.
	"New Optical Metrology for Masks: Range and Accuracy Rivals SEM", Cottle et al., Photomask Japan 2001, Poster 4409-60, April 2001, pp. 1-6.
	"Soft Defect Printability: Correlation to Optical Flux-Area Measurements", Taylor et al., the SPIE 20 <sup>th</sup> Annual BACUS Symposium on Photomask Technology and Management, Conference 4186, September 2000, pp. 1-9.
	"The End of Thresholds: Subwavelength Optical Linewidth Measurement Using the Flux-Area Technique", Fiekowsky, Photomask Japan 2000, Poster 4066-67, April 2000, pp. 1-6.
	"Defect Printability Measurement in the KLA-351: Correlation to Defect Sizing Using the AVI Metrology System", Fiekowsky et al., the SPIE 19 <sup>th</sup> Annual BACUS Symposium on Photomask Technology and Management, Conference 3873, September 1999, pp. 1-7.
	"Accurate and Repeatable Mask Defect Measurements for Quarter-Micron Technology", Fiekowsky, the SPIE 17 <sup>th</sup> Annual BACUS Symposium on Photomask Technology and Management, September 1997, pp. 1-6.
	"The AVI Photomask Metrology System", Automated Visual Inspection Presentation, February 2002, 25 pages

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EXAMINER INITIALS	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE
<i>PI</i>	4,926,489	5/1990	Danielson et al.	382	144	
<i>PI</i>	5,182,718	1/1993	Harafuji et al.	716	21	
<i>PI</i>	5,308,991	5/1994	Kaplan	250	492.22	
<i>PI</i>	5,663,893	9/1997	Wampler et al.	716	19	
<i>PI</i>	5,723,233	3/1998	Garza et al.	430	5	
<i>PI</i>	5,774,222	6/1998	Maeda et al.	356	394	
<i>PI</i>	5,888,675	3/1999	Moore et al.	430	5	
<i>PI</i>	6,077,310	6/2000	Yamamoto et al.	716	19	
<i>PI</i>	6,078,738	6/2000	Garza et al.	716	21	
<i>PI</i>	6,081,659	6/2000	Garza et al.	716	21	
<i>PI</i>	6,120,952	9/2000	Pierrat et al.	430	30	
<i>PI</i>	6,223,139	4/2001	<del>Wong et al.</del> Wang et al.	703	5	
<i>PI</i>	6,226,781	5/2001	Nistler et al.	716	19	
<i>PI</i>	6,243,855	6/2001	Kobayashi et al.	716	19	
<i>PI</i>	6,272,236	8/2001	Pierrat et al.	382	144	

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EXAMINER <i>Shallaka Fike</i>	DATE CONSIDERED <i>11/8/2005</i>
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EXAMINER INITIALS	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE
<i>PS</i>	6,370,679	4/2002	Chang et al.	716	19	
<i>PS</i>	6,449,749	9/2002	Stine	716	4	
<i>PS</i>	6,453,452	9/2002	Chang et al.	716	8	
<i>PS</i>	6,453,457	9/2002	Pierrat et al.	716	19	
<i>PS</i>	6,470,489	10/2002	Chang et al.	716	21	
<i>PS</i>	6,519,501	2/2003	Pierrat et al.	700	121	
<i>PS</i>	6,757,645	6/2004	Chang et al.	703	13	
<i>PS</i>	2004/0225488	11/2004	Wang et al.	703	5	

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